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(71)Applicant: SUMITOMO ELECTRIC IND

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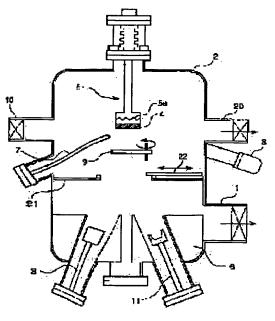
(72)Inventor:

NAKAMURA TAKAO

(54) FORMATION OF OXIDE SUPERCONDUCTING THIN FILM

(57)Abstract:

PURPOSE: To improve the surface cleanliness by supplying an oxidizing gas contg. O2 and the O3 generated by supplying O2 contg. Ar to an ozonizer around the substrate and supplying a component element other than 02 from a K-cell 1 vaporization source to bring about a reaction. CONSTITUTION: A substrate 4 of MgO, etc., is set on a substrate holder 5, and the vaporization sources of Y, Ba, Cu, etc., are set in a K cell 3. and then a vacuum chamber 2 is evacuated to 1 × 10-9Torr. An oxidizing gas contg. O2 Ar and the O3, generated by supplying the O2 contg. 1-5vol.% Ar to an ozonizer is supplied on the film forming surface, and the periphery of the substrate 4 is regulated to about $5 \times 10 - 5$ Torr. The substrate 4 is heated to about 700°C



simultaneously with gas supply, the vaporization source to about 1220°C, Ba to about 628°C and Cu to 1000°C, a shutter 9 is opened when a molecular beam generated from the vaporization source is stabilized, and then the formation of film is started at the rate of about 1nm/min. Heating is stopped when a specified film thickness is reached, the film is cooled, and an oxide superconducting thin film of Y1Ba2Cu3O7-x, etc., having a good surface condition is obtained.

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